

### **REMARKS**

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1-16 are pending in the present application with claim 14 having been amended by the present amendment.

In addition, it is respectfully requested this amendment be entered as it is believed no new issues have been raised. In particular, claim 14 has been amended and includes features already examined in allowed claim 1.

In the outstanding Office Action, claims 14 and 16 were rejected under 35 U.S.C. § 102(b) as anticipated by Harvilchuk et al.; claim 15 was rejected under 35 U.S.C. § 103(a) as unpatentable over Harvilchuk et al. in view of Cleeves; and claims 1-13 were allowed.

Applicants thank the Examiner for the indication of allowable subject matter.

Claims 14 and 16 stand rejected under 35 U.S.C. § 102(b) as anticipated by Harvilchuk et al. This rejection is respectfully traversed.

Independent claim 14 has been amended to clarify that the conductive layer is removed only at portions corresponding to the photoresist layer to form a source/drain electrode. Further, independent claim 14 has also been amended to include the last six steps in allowed independent claim 1.

The amendments to claim 14 are supported at least by Figures 3F-3J. For example, Figure 3F illustrates simultaneously removing the photoresist layer 305 and the conductive layer 306 in which the conductive layer is removed only at portions corresponding to the photoresist layer 305 to form source/drain electrodes 306a and 306b. Figure 3G illustrates forming a passivation layer 307 and forming a second photoresist pattern 308. Figure 3I illustrates side-etching a part of the passivation layer 307 thus to expose a part of the drain electrode 306a. Figure 3I also illustrates forming a pixel electrode material 309 and Figure 3J illustrates simultaneously removing the second photoresist pattern 308 and the pixel electrode material 309

to form a pixel electrode.

It is respectfully noted Harvilchuk et al. does not teach or suggest simultaneously removing a photoresist layer and conductive layer in which the conductive layer is removed only at a portions corresponding to the photoresist layer to form a source/drain electrode nor the step of side-etching a part of the passivation layer to expose a part of the drain electrode as claimed by the present invention.

Accordingly, it is respectfully submitted independent claim 14 and each claim depending therefrom are allowable.

Claim 15 stands rejected under 35 U.S.C § 103(a) as unpatentable over Harvilchuk et al. in view of Cleeves. This rejection is respectfully traversed.

It is respectfully submitted this rejection has also been overcome as claim 15 is a dependent claim and Cleeves also does not teach or suggest the features recited in amended independent claim 14.

### **Conclusion**

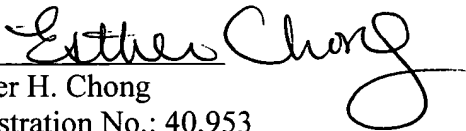
It is believed that a full and complete response has been made to the Office Action. The Examiner is accordingly respectfully requested to place the application in condition for allowance and to issue a Notice of Allowability.

Should there be any outstanding matters that need to be resolved in the present application, the Examiner is respectfully requested to contact David A. Bilodeau (Reg. No. 42,325) at the telephone number of the undersigned below, to conduct an interview in an effort to expedite prosecution in connection with the present application.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37.C.F.R. §§1.16 or 1.14; particularly, extension of time fees.

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Respectfully submitted,

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